1731

PATENT APPLICATION

#6 8-16-01

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of	:	Akira IKUSHIMA, Kazuya SAITO, Takashi MIURA and Shogo NASUDA
Serial no.	:	09/848,246
Filed	:	May 3, 2001
For	:	METHOD OF MANUFACTURING AN OPTICAL FIBER
Group Art Unit	:	1731
Examiner	:	John Hoffmann
Docket	:	ADACHI P163USP2

The Commissioner of Patents and Trademarks
Washington, D.C. 20231

INFORMATION DISCLOSURE STATEMENT

Dear Sir:

In connection with this matter, the Applicant hereby attaches one (1) United States Patent Office Form PTO-1449 and copies of the information listed in the enclosed PTO-1449 Form, unless otherwise indicated on such Form.

The relevance of the uncovered citations is indicated on page 2 of the specification and English language abstract, of all of the listed relevant foreign language information, is submitted herewith.

In the event that there are any fee deficiencies or additional fees are payable, please charge the same or credit any overpayment to our Deposit Account (Account No. 04-0213).

Respectfully submitted,

Michael J. Bujold, Reg. No. 32,018
Customer No. 020210
Davis & Bujold, P.L.L.C.
Fourth Floor
500 North Commercial Street
Manchester NH 03101-1151
Telephone 603-624-9220
Facsimile 603-624-9229
E-mail: patent@davisandbujold.com

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service, with sufficient postage, as First Class Mail in an envelope addressed to: Commissioner of Patents and Trademarks, Washington, D.C. 20231 on August 8, 2001 .

By: _____
Print Name: Michael J. Bujold

PATENT ABSTRACTS OF JAPAN

04342427

November 27, 1992

PRODUCTION OF HIGH-LEVEL OH GROUP-CONTAINING SILICA GLASS

INVENTOR: SETO KATSUYUKI; SHAMOTO NAOKI; TSUMANUMA KOUJI; SANADA KAZUO

APPL-NO: 03139446 (JP 91139446)

FILED: May 16, 1991

ASSIGNEE: FUJIKURA LTD

INT-CL: C03B8/04, (Section C, Class 03, Sub-class B, Group 8, Sub-group 04); C03B20/00, (Section C, Class 03, Sub-class B, Group 20, Sub-group 00); C03B37/018, (Section C, Class 03, Sub-class B, Group 37, Sub-group 018); C03C3/06, (Section C, Class 03, Sub-class C, Group 3, Sub-group 06); G02B6/00, (Section G, Class 02, Sub-class B, Group 6, Sub-group 00)

ABST:

PURPOSE: To provide the title glass suitable for the transmission of ultraviolet region.

CONSTITUTION: An Si compound such as SiCl[4] is fed into an oxyhydrogen flame together with H[2]O vapor to produce fine silica glass particles, which are, in turn, heated at high temperatures into a transparent glass. Specifically, using a concentric multitubular burner 2, the central port is fed with an Si compound such as SiCl[4], its outside with H[2] gas, Ar gas and O[2] gas, and the outermost layer with H[2]O vapor. The fine silica glass particles containing a large quantity of OH group produced in the oxyhydrogen flame 3 are accumulated at the tip of or around a rod 1 as a preform 5. This preform is then made into a transparent glass, thus obtaining the objective glass containing OH group at a level of 800-1000ppm or so.

PATENT ABSTRACTS OF JAPAN

04342436

November 27, 1992

PRODUCTION OF SILICA GLASS WITH HIGH HYDROXYL GROUP CONCENTRATION AND SILICA GLASS WITH HIGH HYDROXYL GROUP CONCENTRATION OBTAINED THEREBY

INVENTOR: SANADA KAZUO; CHIGIRA SADAO; KANEDA KEIJI

APPL-NO: 03141142 (JP 91141142)

FILED: May 16, 1991

ASSIGNEE: FUJIKURA LTD

INT-CL: C03C3/06, (Section C, Class 03, Sub-class C, Group 3, Sub-group 06); C03B20/00, (Section C, Class 03, Sub-class B, Group 20, Sub-group 00); C03C4/00, (Section C, Class 03, Sub-class C, Group 4, Sub-group 00); C03C23/00, (Section C, Class 03, Sub-class C, Group 23, Sub-group 00)

ABST:

PURPOSE: To obtain a silica glass having an ultrahigh hydroxyl group content of >= 0.2wt. % and excellent characteristics of ultraviolet ray and radiation resistances.

CONSTITUTION: Silica glass is held in a hydrogen atmosphere and exposed to radiation. In the process, heating is preferably carried out to increase the rate of reaction. Silica glass having 0.2-10wt. % hydroxyl group concentration is obtained according to the aforementioned method.